



2881

#71 1/2 / E

Patent
USSN 09/375,267
Atty Docket 99108

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

HANS LOSCHNER, ET AL.

For: PARTICLE MULTIBEAM LITHOGRAPHY

Serial No. 09/375,267

Filed: August 17, 1999

Group Art Unit:
2881

Examiner:
Anthony Quash

RECEIVED
JUN - 5 2001
TECHNOLOGY CENTER 2600

SUPPLEMENTAL AMENDMENT B

TO:
Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sir:

Supplementing Amendment A, applicant requests that the subject application be amended as follows:

IN THE CLAIMS:

Please amend claim 1 in the manner set forth below. A clean copy of claim 4 is attached herewith.

1. (Amended) An apparatus for multibeam lithography by means of electrically charged particles, comprising an illumination system having a particle source, the illumination system producing an illuminating beam of said electrically charged particles, and a multibeam optical system positioned after the illumination system as seen in the direction of the beam, said multibeam optical system comprising at least one aperture plate having an array of a plurality of apertures to form a plurality of sub-beams, wherein the multibeam optical system focuses the sub-beams onto the surface of a substrate,

wherein for each sub-beam a deflection unit is provided, said deflection unit being positioned within the multibeam optical system and adapted to correct

CERTIFICATE OF MAILING	
I hereby certify that this correspondence is being deposited with the United States Postal Service on first-class mail in an envelope addressed for Assistant Commissioner of Patents and Trademarks, Washington, DC 20231 on:	
Date	5/26/01